

# SPECIFICATION

TO ALL WHOM IT MAY CONCERN:

BE IT KNOWN THAT I, HIROSHI KONDOH, a citizen of Japan residing at Kanagawa, Japan has invented certain new and useful improvements in

SEMICONDUCTOR DEVICE, EL DISPLAY DEVICE, LIQUID CRYSTAL DISPLAY DEVICE, AND CALCULATING DEVICE

of which the following is a specification:-

## BACKGROUND OF THE INVENTION

### 1. Field of the Invention

The present invention relates to a semiconductor device able to improve a mobility of carriers, and an EL (electroluminescent) display device, a liquid crystal display device, and a calculating device utilizing the semiconductor device.

### 2. Description of the Related Art

There are various kinds of display apparatuses in the related art, and CRT (cathode-ray tube) displays, liquid crystal displays, and EL (electroluminescence) displays are typical ones. The CRT displays are widely used so far because of their high display quality and lower manufacturing cost. Nevertheless, a CRT display suffers from the difficulties of reducing the size and lowering the electric power consumption of the cathode-ray tube. For these reasons, demand for the liquid crystal displays and the EL displays rapidly increases. Especially, because of such features as self-emitting, low driving voltages, and high brightness, more and more expectations are placed on the organic EL display devices used in the EL displays.

The liquid crystal displays are widely used because of their good visibility and fast responding

performance. Meanwhile, the EL displays, which exhibit good visibility and responding performance, are also being widely spread gradually. Further, the liquid crystal displays and the EL displays both have lower  
5 power consumption than that of the CRT displays.

In the above displays, one of the commonly used active devices is a transistor including an organic semiconductor layer, a source electrode (first electrode), a drain electrode (second electrode), and a  
10 gate electrode (third electrode). FIG. 27 and FIG. 28 are sectional views each showing a TFT (Thin Film Transistor), specifically, a thin film FET (Field Effect Transistor) of the related art.

In the thin film FET shown in FIG. 27, a  
15 source electrode 203 and a drain electrode 204 are separated by an electrically-neutral organic semiconductor layer 205 (channel region), and are arranged in the same plane. The gate electrode 201 is electrically separated from the organic semiconductor  
20 layer 205 by a gate insulating layer 202.

In the thin film FET shown in FIG. 28, a source electrode 213 and a drain electrode 214 are arranged to be separated at a distance in the same plane on an organic semiconductor layer 215. The gate  
25 electrode 211 is electrically separated from the

organic semiconductor layer 215 by a gate insulating layer 212.

In these thin film FETs of the related art, the organic semiconductor layer can be formed by coating, so it is possible to largely reduce the fabricating cost. However, there exists a problem in that the charge mobility of an organic semiconductor material is much lower than that of an inorganic semiconductor material. In recent years, the organic semiconductor material Polythiophene is found to be of high charge mobility (Applied Physics Letter, vol.69, p4108(1996)), and therefore is attracting attention, but its charge mobility is less than  $0.1 \text{ (cm}^2/\text{V}\cdot\text{sec)}$ , about one order of magnitude lower than that of the current amorphous silicon. Furthermore, the switching speed of an active device using the organic semiconductor material generally is of the order of KHz, and is not suitable for driving devices for displaying fine motion pictures.

In the related art, in order to increase the switching speed of an active device, in addition to improving the mobility of an organic semiconductor material, attempts have also been made in shortening the channel length of the active device. It was considered that the current flowing in the

semiconductor layer would increase if the channel length was shortened, and thus the organic thin film transistor (TFT) could be used to drive an EL display. However, in order to pattern a channel length (that is, 5 the source-drain distance) less than a few  $\mu\text{m}$ , complicated photolithography processing is needed, and thus the fabricating costs goes up.

To solve this problem, the static induction transistor (SIT), in which a source electrode, a gate 10 electrode, and a drain electrode are stacked vertically in sequence, was presented in the ninth lecture course of Bioelectronics Division of Applied Physics Association (2001).

FIGs. 29A and 29B are sectional views 15 showing static induction transistors (SIT) of the related art. FIG. 29A shows a state in which a voltage is not applied, and FIG. 29B shows a state in which a voltage is applied and a depletion region is formed. As shown in FIG. 29A and 29B, in a SIT active device of 20 the related art, a source electrode 223, an organic semiconductor layer 225, and a drain electrode 224 are stacked vertically in sequence, and in the center portion of the organic semiconductor layer 225, several rod-shaped gate electrodes 222 are formed in a row at 25 certain intervals and approximately in parallel with

the source electrode 223 and the drain electrode 224.  
With this compound organic EL transistor, as shown in  
FIG. 29B, if a gate voltage is applied to the gate  
electrode 222, the depletion region in the organic  
5 semiconductor layer 225 expands, and the resistance  
between the source electrode 223 and the drain  
electrode 224 increases, thereby the current between  
the gate electrode 222 and the drain electrode 224 is  
switched ON or OFF. With such an SIT, the area of the  
10 active device can be reduced.

As shown in FIG. 29A and 29B, because the  
channel length of the SIT can be controlled by using  
the film thickness of the semiconductor layer, it is  
possible to form a thin semiconductor layer by coating  
15 or other film fabrication techniques, so the SIT is  
expected to work as a transistor capable of fast  
response in the future.

Turning to the problem addressed by the  
present invention, however, in the above SIT, when a  
20 gate voltage is not applied to the gate electrode 222,  
a current flows between the source electrode 223 and  
the drain electrode 224; when a gate voltage is applied  
to the gate electrode 222, the current between the  
source electrode 223 and the drain electrode 224 is  
25 switched off (that is, such a SIT is a normally ON type

transistor).

Further, with the current film fabrication technique, the film thickness of the organic semiconductor layer 225 is thicker than that of the organic semiconductor layer 215 in the TFT of the related art as shown in FIG. 28, and as a result, the channel length between the source electrode 223 and the drain electrode 224 in the above SIT is shorter than that of the TFT of the related art. Therefore, in the SIT, the resistance between the source electrode 223 and the drain electrode 224 decreases, and there arises a problem in that the current in an OFF state is large.

#### SUMMARY OF THE INVENTION

Accordingly, it is a general object of the present invention to solve the above problems of the related art.

A more specific object of the present invention is to provide a semiconductor device able to increase a mobility of carriers and reduce a current in an OFF state, and an EL display device, a liquid crystal display device, and a calculating device utilizing the semiconductor device.

To attain the above object, according to a first aspect of the present invention, there is

provided a semiconductor device comprising a gate electrode, an insulating layer on the gate electrode, a first electrode on the insulating layer, a second electrode on the insulating layer at an interval with  
5 the first electrode, an organic semiconductor layer disposed in the interval between the first electrode and the second electrode and covering at least part of the first electrode and the second electrode, and a first resistance layer formed on the organic  
10 semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer.

In the above semiconductor device,  
preferably, both a distance from the first electrode to  
15 the first resistance layer, and a distance from the second electrode to the first resistance layer are shorter than the interval between the first electrode and the second electrode.

Further, one of the first electrode and the  
20 second electrode may be in contact with the first resistance layer.

Further, the semiconductor device further comprises a second resistance layer formed at least at one of the position between the first resistance layer  
25 and the organic semiconductor layer, the position



between the first electrode and the organic semiconductor layer, and the position between the second electrode and the organic semiconductor layer, wherein the second resistance layer has an electrical resistance so that carriers in the organic semiconductor layer are allowed to tunnel through the second resistance layer when a voltage of a predetermined value or more than the predetermined value is applied across the second resistance layer.

10            Preferably, in the above semiconductor device, at least one of the first electrode, the second electrode and the first resistance layer is in contact with the organic semiconductor layer, and an interface between one of the first electrode, the second  
15    electrode and the first resistance layer rectifies an electrical current therethrough.

Further, the first resistance layer may be formed to be one of a plate shape, an inter-digital shape, a grating shape, and a disk shape.

20            Further, a substrate may be beneath the gate electrode.

Preferably, the organic semiconductor layer is formed from at least one organic material selected from the group consisting of poly(N-vinylcarbazole)  
25    derivatives, poly( $\gamma$ -(carbazolyethyl)glutamate)

derivatives, poly(vinylphenanthrene) derivatives,  
polysilane derivatives, oxazole derivatives, oxadiazole  
derivatives, imidazole derivatives, arylamine  
derivatives such as monoarylamine derivatives and  
5 triarylamine derivatives, benzidine derivatives,  
diarylmethane derivatives, triarylmethane derivatives,  
styrylanthracene derivatives, pyrazoline derivatives,  
divinylbenzene derivatives, hydrazone derivatives,  
indene derivatives, indenone derivatives, butadiene  
10 derivatives, pyrene derivatives such as pyrene-  
folmaldehyde and poly(vinylpyrene), stilbene  
derivatives such as  $\alpha$ -phenylstilbene derivatives, and  
bis-stilbene derivatives, enamine derivatives,  
fluorenone and derivatives thereof, poly(fluorenone)  
15 and derivatives thereof, and thiophene derivatives such  
as poly(alkylthiophene), or at least one organic  
material selected from the group consisting of  
pentacene, tetracene, bis-azo pigments, tris-azo  
pigments, poly-azo pigments, triarylmethane-based  
20 pigments, thiazine-based pigments, oxazine-based  
pigments, xanthene-based pigments, cyanine pigments,  
styryl pigments, pyrylium-based pigments, quinacridone-  
based pigments, indigo-based pigments, perylene-based  
pigments, polycyclic quinone-based pigments,  
25 bis(benzimidazole)-based pigments, indanthrone-based

pigments, squarylium-based pigments, anthraquinone-based pigments, and phthalocyanine-based pigments such as copper phthalocyanine and titanylphthalocyanine.

Preferably, the first resistance layer is  
5 formed from at least one electrically conductive material of polyacetylene-based electrically conductive polymers, polyphenylene-based electrically conductive polymers such as poly(para-phenylene) and derivatives thereof and poly(phenylene vinylene) and derivatives  
10 thereof, heterocyclic electrically conductive polymers such as polypyrrole and derivatives thereof, polythiophene and derivatives thereof, poly(ethylenedioxythiophene) and derivatives thereof, and polyfuran and derivatives thereof, ionic  
15 electrically conductive polymers such as polyaniline and derivatives thereof, and metals of chromium (Cr), tantalum (Ta), titanium (Ti), copper (Cu), aluminum (Al), molybdenum (Mo), tungsten (W), nickel (Ni), gold (Au), palladium (Pd), platinum (Pt), silver (Ag), and  
20 tin (Sn).

Preferably, the first resistance layer includes at least one dopant with a low vapor pressure including one or more poly(sulfonic acid), poly(styrenesulfonic acid), naphthalenesulfonic acid,  
25 and alkyl naphthalenesulfonic acid.

Preferably, each of the first electrode, the second electrode, and the gate electrode is formed from at least one or more metals of chromium (Cr), tantalum (Ta), titanium (Ti), copper (Cu), aluminum (Al),  
5 molybdenum (Mo), tungsten (W), nickel (Ni), gold (Au), palladium (Pd), platinum (Pt), silver (Ag), and tin (Sn), or at least one electrically conductive polymer selected from the group including polyacetylene-based electrically conductive polymers, polyphenylene-based  
10 electrically conductive polymers such as poly(para-phenylene) and derivatives thereof and poly(phenylene vinylene) and derivatives thereof, heterocyclic electrically conductive polymers such as polypyrrole and derivatives thereof, polythiophene and derivatives  
15 thereof, poly(ethylenedioxythiophene) and derivatives thereof, and polyfuran and derivatives thereof, and ionic electrically conductive polymers such as polyaniline and derivatives thereof.

Preferably, the insulating layer is formed  
20 from at least one resin selected from the group consisting of thermoplastic resins such as styrene-based polymers such as copoly(styrene/butadiene), copoly(styrene/acrylonitrile), terpoly(styrene/acrylonitrile/butadiene),  
25 copoly(styrene/maleic acid), and copoly(styrene/acrylic

acid), polyethylene-based resins such as  
copoly(ethylene/vinyl acetate), and chlorinated  
polyethylenes, polypropylene, vinyl chloride-based  
resins such as copoly(vinyl chloride/vinyl acetate),  
5 polyester alkyd resins, polyamides, polyurethanes,  
polycarbonates, polyallylates, polysulfones, diallyl  
phthalate resin, poly(vinylbutyral) resin, polyether  
resins, polyester resins, acrylic resin, silicone resin,  
epoxy resins, phenolic resin, urea resin, melamine  
10 resin, fluorocarbon resins such as PFA, PTFE, and PVDF,  
Parylene resin, polyimide resins, and photo-setting  
resins such as epoxyacrylates and urethane acrylates,  
or a metal oxide produced via oxidation of a surface of  
an electrode layer formed from the metal.

15 Preferably, the insulating layer is formed  
from a metal oxide film produced by coating and baking  
a solution obtained via hydrolysis of a metal alkoxide  
represented by one of the general formulas  $M(OR)_n$  and  
 $MR(OR')_{n-1}$ , wherein each of R and R' is an organic group  
20 such as an alkyl group and a phenyl group, M is a metal  
in one of IVA through VIIA groups, VIII group, and IB  
through VIB groups of the periodic table, and n is an  
ionic valence of the metal M.

Preferably, the second resistance layer is  
25 formed from at least one resin selected from the group

consisting of thermoplastic resins such as styrene-based polymers such as copoly(styrene/butadiene), copoly(styrene/acrylonitrile), terpoly(styrene/acrylonitrile/butadiene),  
5 copoly(styrene/maleic acid), and copoly(styrene/acrylic acid), polyethylene-based resins such as copoly(ethylene/vinyl acetate), and chlorinated polyethylenes, polypropylene, vinyl chloride-based resins such as copoly(vinyl chloride/vinyl acetate),  
10 polyester alkyd resins, polyamides, polyurethanes, polycarbonates, polyallylates, polysulfones, diallyl phthalate resin, poly(vinylbutyral) resin, polyether resins, polyester resins, acrylic resin, silicone resin, epoxy resins, phenolic resin, urea resin, melamine  
15 resin, fluorocarbon resins such as PFA, PTFE, and PVDF, Parylene resin, polyimide resins, and photo-setting resins such as epoxyacrylates and urethane acrylates, or a metal oxide produced via oxidation of a surface of at least one of the first electrode and the second  
20 electrode.

Preferably, the second resistance layer is formed from a metal oxide film produced by coating and baking a solution obtained via hydrolysis of a metal alkoxide represented by one of the general formulas  
25  $M(OR)_n$  and  $MR(OR')_{n-1}$ , wherein each of R and R' is an

organic group such as an alkyl group and a phenyl group, M is a metal in one of IVA through VIIA groups, VIII group, and IB through VIB groups of the periodic table, and n is an ionic valence of the metal M.

5                    Preferably, the organic semiconductor layer includes a dielectric material. More preferably, the dielectric material is selected from styrene-based polymers such as copoly(styrene/butadiene), copoly(styrene/acrylonitrile),  
10    terpoly(styrene/acrylonitrile/butadiene), copoly(styrene/maleic acid), and copoly(styrene/acrylic acid), polyethylene-based resins such as copoly(ethylene/vinyl acetate), and chlorinated polyethylenes, polypropylene, vinyl chloride-based  
15    resins such as copoly(vinyl chloride/vinyl acetate), polyester alkyd resins, polyamides, polyurethanes, polycarbonates, polyallylates, polysulfones, diallyl phthalate resin, poly(vinylbutyral) resin, polyether resins, polyester resins, acrylic resin, silicone resin,  
20    epoxy resins, phenolic resin, urea resin, melamine resin, fluorocarbon resins such as PFA, PTFE, and PVDF, Parylene resin, polyimide resins, and photo-setting resins such as epoxyacrylates and urethane acrylates, a metal oxide film produced by baking a solution obtained  
25    via hydrolysis of a metal alkoxide represented by one

of the general formulas  $M(OR)_n$  and  $MR(OR')_{n-1}$ , in which each of R and R' is an organic group such as an alkyl group and a phenyl group, M is a metal in one of IVA through VIIA groups, VIII group, and IB through VIB groups of the periodic table, and n is an ionic valence of the metal M, an oxide of one of Al, Ta, W, and Si, and a nitride of Si.

To attain the above object, according to a second aspect of the present invention, there is provided a semiconductor device comprising a first electrode, a second electrode at an interval with the first electrode, an organic semiconductor layer disposed in the interval between the first electrode and the second electrode and covering at least part of the first electrode and the second electrode, a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer, an insulating layer on the first resistance layer, and a gate electrode on the insulating layer.

Preferably, the semiconductor device further comprises a second resistance layer formed on at least one of an interface between the first resistance layer and the organic semiconductor layer, an interface between the first electrode and the organic



semiconductor layer, and an interface between the second electrode and the organic semiconductor layer; the second resistance layer has a resistance so that carriers in the organic semiconductor layer are allowed  
5 to tunnel through the second resistance layer when a voltage of a predetermined value or more than the predetermined value is applied across the second resistance layer.

Further, a substrate may be beneath the  
10 first electrode, the second electrode and the organic semiconductor layer.

To attain the above object, according to a third aspect of the present invention, there is provided a semiconductor device comprising an organic  
15 semiconductor layer, a first resistance layer beneath the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer, a first electrode on the organic semiconductor layer, a second  
20 electrode on the organic semiconductor layer at an interval with the first electrode, an insulating layer disposed in the interval between the first electrode and the second electrode and covering the first electrode and the second electrode, and a gate  
25 electrode on the insulating layer, wherein the first

resistance layer has an electrical resistance lower than an electrical resistance of the organic semiconductor layer.

Preferably, the semiconductor device further  
5 comprises a second resistance layer formed on at least one of an interface between the first resistance layer and the organic semiconductor layer, an interface between the first electrode and the organic semiconductor layer, and an interface between the  
10 second electrode and the organic semiconductor layer; the second resistance layer has a resistance so that carriers in the organic semiconductor layer are allowed to tunnel through the second resistance layer when a voltage of a predetermined value or more than the  
15 predetermined value is applied across the second resistance layer.

Further, a substrate may be beneath the first resistance layer.

To attain the above object, according to a  
20 fourth aspect of the present invention, there is provided a semiconductor device comprising a gate electrode, an insulating layer on the gate electrode, a first resistance layer on the insulating layer, an organic semiconductor layer on the first resistance  
25 layer, a first electrode on the organic semiconductor

layer, and a second electrode on the organic semiconductor layer at an interval with the first electrode, wherein the first resistance layer has an electrical resistance lower than an electrical resistance of the organic semiconductor layer.

Preferably, in the above semiconductor device, two opposite ends of the first resistance layer may be covered by the organic semiconductor layer.

Further, the above semiconductor device further includes a second resistance layer formed at least at one of the position between the first resistance layer and the organic semiconductor layer, the position between the first electrode and the organic semiconductor layer, and the position between the second electrode and the organic semiconductor layer, wherein the second resistance layer has an electrical resistance so that carriers in the organic semiconductor layer are allowed to tunnel through the second resistance layer when a voltage of a predetermined value or more than the predetermined value is applied across the second resistance layer.

To attain the above object, according to a fifth aspect of the present invention, there is provided an electroluminescent display device, comprising a plurality of semiconductor devices, each

semiconductor device including a gate electrode, an insulating layer on the gate electrode, a first electrode on the insulating layer, a second electrode on the insulating layer at an interval with the first  
5 electrode, an organic semiconductor layer disposed in the interval between the first electrode and the second electrode and covering at least part of the first electrode and the second electrode, and a first resistance layer formed on the organic semiconductor  
10 layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer.

To attain the above object, according to a sixth aspect of the present invention, there is  
15 provided an electroluminescent display device including a plurality of semiconductor devices and a plurality of light emitting elements arranged in a matrix manner on a substrate, each of the semiconductor devices comprising a gate electrode on the substrate, an  
20 insulating layer covering ends and a surface of the gate electrode, a first electrode on the insulating layer, a second electrode on the insulating layer at an interval with the first electrode, an organic semiconductor layer disposed in the interval between  
25 the first electrode and the second electrode and

covering at least part of the first electrode and the second electrode, and a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer; the  
5 light emitting element comprising a transparent electrode on the substrate, an electroluminescent layer on the transparent electrode, and a cathode on the electroluminescent layer, wherein the first electrode  
10 is electrically connected with the transparent electrode.

To attain the above object, according to a seventh aspect of the present invention, there is provided a liquid crystal display device comprising a  
15 semiconductor device including a gate electrode, an insulating layer on the gate electrode, a first electrode on the insulating layer, a second electrode on the insulating layer at an interval with the first electrode, an organic semiconductor layer disposed in  
20 the interval between the first electrode and the second electrode and covering at least part of the first electrode and the second electrode, and a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an  
25 electrical resistance of the organic semiconductor

layer.

To attain the above object, according to an eighth aspect of the present invention, there is provided a calculating device, comprising at least one  
5 of a NOT circuit, a NAND circuit, and a NOR circuit each including a plurality of semiconductor devices, each of the semiconductor devices including a gate electrode, an insulating layer on the gate electrode, a first electrode on the insulating layer, a second  
10 electrode on the insulating layer at an interval with the first electrode, an organic semiconductor layer disposed in the interval between the first electrode and the second electrode and covering at least part of the first electrode and the second electrode, and a  
15 first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer.

These and other objects, features, and  
20 advantages of the present invention will become more apparent from the following detailed description of preferred embodiments given with reference to the accompanying drawings.

25 BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 is a sectional view showing a configuration of an active device 20 according to a first embodiment of the present invention;

FIGs. 2A and 2B are perspective views of active devices according to the first embodiment of the present invention, where FIG. 2A shows an active device having a plate-shaped low resistance layer, and FIG. 2B shows an active device having an inter-digital shaped low resistance layer;

FIG. 3 is a sectional view of the active device 20 in FIG. 1 connected to power supplies;

FIG. 4 is a sectional view showing a configuration of an active device 20a according to a second embodiment of the present invention;

FIG. 5 shows a chemical formula representing an organic semiconductor material used in the second embodiment of the present invention;

FIG. 6 is a sectional view of a configuration of an active device 30 according to a third embodiment of the present invention;

FIG. 7 is a sectional view of a configuration of an active device 40 according to a fourth embodiment of the present invention;

FIG. 8 is a sectional view for explaining the fabrication steps of the active device in FIG. 7;

FIG. 9 is a partial sectional view of the active 40 connected with power supplies;

FIG. 10 is a sectional view of a configuration of an active device 50 according to a fifth embodiment of the present invention;

FIGs. 11A through 11C are graphs showing rectification performance of the active device according to the fifth embodiment of the present invention;

FIG. 12 is a sectional view of an active device according to a sixth embodiment of the present invention;

FIG. 13 is a sectional view of another configuration of the active device of the sixth embodiment of the present invention;

FIG. 14 is a sectional view of an active device according to a seventh embodiment of the present invention;

FIG. 15 is a sectional view of another configuration of the active device according to the seventh embodiment of the present invention;

FIG. 16 is a sectional view of an active device according to an eighth embodiment of the present invention;

FIG. 17 is a sectional view of another



configuration of the active device according to the eighth embodiment of the present invention;

FIG. 18 is a sectional view of another configuration of the active device according to the eighth embodiment of the present invention;

FIG. 19 is a partial sectional view of an EL display device according to a ninth embodiment of the present invention;

FIG. 20 is a circuit diagram of a liquid crystal display device according to a 10th embodiment of the present invention;

FIGs. 21A through 21C are logic circuits of a calculating device according to an 11th embodiment of the present invention, where FIG. 21A shows a NOT circuit, FIG. 21B shows a NAND circuit, and FIG. 21C shows a NOR circuit;

FIG. 22 is a partial sectional view of a first example of the active device of the present invention;

FIG. 23 is a partial sectional view of a third example of the active device of the present invention;

FIG. 24 is a view of a table showing evaluation results of the first and the second examples of the active device of the present invention;

FIG. 25 is a view of a table showing evaluation results of the third and the fourth examples of the active device of the present invention;

FIG. 26 is a view of a table showing  
5 evaluation results of the fifth example of the active device of the present invention;

FIG. 27 is a sectional view showing an example of a thin film field effect transistor of the related art;

10 FIG. 28 is a sectional view showing another example of a thin film field effect transistor of the related art; and

FIGs. 29A and 29B are sectional views showing static induction transistors of the related art.

15

#### DESCRIPTION OF THE PREFERRED EMBODIMENTS

Below, preferred embodiments of the present invention will be explained with reference to the accompanying drawings. Note that in the following  
20 descriptions, the same reference numerals are used for the same elements, the elements indicated by the same reference numerals are formed from the same materials, and the overlapping descriptions are omitted.

25

#### The First Embodiment

FIG. 1 shows a sectional view of an active device 20 according to a first embodiment of the present invention.

As shown in FIG. 1, the active device 20 includes a gate electrode 1, an insulating layer 2 (gate insulating film) on the gate electrode 1, a first electrode 3 (source electrode) and a second electrode 4 (drain electrode) on the insulating layer 2 arranged at an interval in the same plane, an organic semiconductor layer 5 disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the upper surfaces of the source electrode 3 and the drain electrode 4, and a low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5 and formed above the organic semiconductor layer 5.

FIGs. 2A and 2B are perspective views of examples of the active device according to the first embodiment of the present invention.

Preferably, the low resistance layer 6 is a plate-shaped layer 6a as shown in FIG. 2A, or an interdigital shaped layer 6b as shown in FIG. 2B, or, although not illustrated, it can be formed to have a grating shape, or a disk shape.

Preferably, the low resistance layer 6 is

formed from, for example, at least one electrically  
conductive material selected from the group including  
polyacetylene-based electrically conductive polymers,  
polyphenylene-based electrically conductive polymers  
5 such as poly(para-phenylene) and derivatives thereof  
and poly(phenylene vinylene) and derivatives thereof,  
heterocyclic electrically conductive polymers such as  
polypyrrole and derivatives thereof, polythiophene and  
derivatives thereof, poly(ethylenedioxythiophene) and  
10 derivatives thereof, and polyfuran and derivatives  
thereof, ionic electrically conductive polymers such as  
polyaniline and derivatives thereof, and metals of  
chromium (Cr), tantalum (Ta), titanium (Ti), copper  
(Cu), aluminum (Al), molybdenum (Mo), tungsten (W),  
15 nickel (Ni), gold (Au), palladium (Pd), platinum (Pt),  
silver (Ag), and tin (Sn).

The above-mentioned electrically conductive  
polymer may include, for example, at least one dopant  
with a low vapor pressure selected from the group  
20 including poly(sulfonic acid), poly(styrenesulfonic  
acid), naphthalenesulfonic acid, and  
alkylnaphthalenesulfonic acid.

As will be appreciated, the low resistance  
layer 6 may also be formed from other materials that  
25 realize the effects of the present invention.

As shown above, since the low resistance layer 6 is formed from conductive polymers, coating can be used to form the low resistance layer 6, and this can effectively reduce the costs of the manufacturing equipment and the device. In case the low resistance layer 6 is formed from the metals mentioned above, the same effect as the above is achievable by forming the low resistance layer 6 by coating using a coating solution prepared by making the metals into highly fine particles and dispersing the fine particles in water or an organic solvent.

In addition, the low resistance layer 6 may also be formed by after-treatment. For example, when using the semiconductor material which is found to be conductive after oxygen being doped, the low resistance layer 6 can be formed on the surface of the organic semiconductor layer 5 after the surface of the organic semiconductor layer 5 is heat-treated in an oxygen atmosphere.

Preferably, the organic semiconductor layer 5 is formed from, for example, at least one organic material selected from the group consisting of poly(N-vinylcarbazole) derivatives, poly( $\gamma$ -(carbazolyethyl)glutamate) derivatives, poly(vinylphenanthrene) derivatives, polysilane

derivatives, oxazole derivatives, oxadiazole derivatives, imidazole derivatives, arylamine derivatives such as monoarylamine derivatives and triarylamine derivatives, benzidine derivatives, 5 diarylmethane derivatives, triarylmethane derivatives, styrylanthracene derivatives, pyrazoline derivatives, divinylbenzene derivatives, hydrazone derivatives, indene derivatives, indenone derivatives, butadiene derivatives, pyrene derivatives such as pyrene- 10 folmaldehyde and poly(vinylpyrene), stilbene derivatives such as  $\alpha$ -phenylstilbene derivatives, and bis-stilbene derivatives, enamine derivatives, fluorenone and derivatives thereof, poly(fluorenone) and derivatives thereof, and thiophene derivatives such 15 as poly(alkylthiophene), or at least one organic material selected from the group consisting of pentacene, tetracene, bis-azo pigments, tris-azo pigments, poly-azo pigments, triarylmethane-based pigments, thiazine-based pigments, oxazine-based 20 pigments, xanthene-based pigments, cyanine pigments, styryl pigments, pyrylium-based pigments, quinacridone-based pigments, indigo-based pigments, perylene-based pigments, polycyclic quinone-based pigments, bis(benzimidazole)-based pigments, indanthrone-based 25 pigments, squarylium-based pigments, anthraquinone-

based pigments, and phthalocyanine-based pigments such as copper phthalocyanine and titanylphthalocyanine.

As shown above, since the organic semiconductor layer 5 is formed from organic materials, vaporization or coating can be used to form the organic semiconductor layer 5, and this can effectively reduce the costs of the manufacturing equipment and the device.

Preferably, the source electrode 3, drain electrode 4, and the gate electrode 1 are formed from, for example, a metal selected from the group including chromium (Cr), tantalum (Ta), titanium (Ti), copper (Cu), aluminum (Al), molybdenum (Mo), tungsten (W), nickel (Ni), gold (Au), palladium (Pd), platinum (Pt), silver (Ag), and tin (Sn), or at least one electrically conductive polymer selected from the group including polyacetylene-based electrically conductive polymers, polyphenylene-based electrically conductive polymers such as poly(para-phenylene) and derivatives thereof and poly(phenylene vinylene) and derivatives thereof, heterocyclic electrically conductive polymers such as polypyrrole and derivatives thereof, polythiophene and derivatives thereof, poly(ethylenedioxythiophene) and derivatives thereof, and polyfuran and derivatives thereof, and ionic electrically conductive polymers such as polyaniline and derivatives thereof.

Preferably, the insulating layer 2 is formed from, for example, at least one resin selected from the group including thermoplastic resins such as styrene-based polymers such as copoly(styrene/butadiene),  
5 copoly(styrene/acrylonitrile),  
terpoly(styrene/acrylonitrile/butadiene),  
copoly(styrene/maleic acid), and copoly(styrene/acrylic acid), polyethylene-based resins such as  
copoly(ethylene/vinyl acetate), and chlorinated  
10 polyethylenes, polypropylene, vinyl chloride-based  
resins such as copoly(vinyl chloride/vinyl acetate),  
polyester alkyd resins, polyamides, polyurethanes,  
polycarbonates, polyallylates, polysulfones, diallyl  
phthalate resin, poly(vinylbutyral) resin, polyether  
15 resins, polyester resins, acrylic resin, silicone resin,  
epoxy resins, phenolic resin, urea resin, melamine  
resin, fluorocarbon resins such as PFA, PTFE, and PVDF,  
Parylene resin, polyimide resins, and photo-setting  
resins such as epoxyacrylates and urethane acrylates,  
20 or a metal oxide produced via oxidation of a surface of  
an electrode layer formed from the metal.

As shown above, since the insulating layer 2 is formed from polymers, coating or other techniques can be used to form the layer 2. In addition, the  
25 insulating layer 2 may also be formed, for example, by



surface oxidation of the electrode layer, which results in reduced costs in the manufacturing equipment and the device.

Alternatively, the insulating layer 2 may be  
5 formed from a metal oxide film produced by coating and baking a solution obtained via hydrolysis of a known metal alkoxide represented by one of the general formulas  $M(OR)_n$  and  $MR(OR')_{n-1}$ , wherein each of R and R' is an organic group such as an alkyl group and a phenyl  
10 group, M is a metal in one of IVA through VIIA groups, VIII group, and IB through VIB groups of the periodic table, and n is an ionic valence of the metal M.

As described above, the insulating layer 2 is formed from metal oxide films obtained by coating or  
15 heat-drying the solution produced in hydrolysis of metal alkoxide, so the insulating layer 2 can be formed without the complicated vacuum processing, which results in reduced costs in the manufacturing equipment and the device.

20 Particularly, since a polyimide resin has both good electric resistance and good solvent resistance characteristics, a polyimide resin may be preferably used as the insulating layer 2 and the high resistance layer 7, and even if a material dissolved or  
25 dispersed in an organic solvent is applied on the resin,

the resin is not be seriously damaged.

In the active device 20 of the present embodiment, the low resistance layer 6 that has an electrical resistance lower than that of the organic semiconductor layer 5 is formed to cover the whole channel region, so it is possible to make the channel short. In the active device 20, if the channel is made short, the distance that carriers move becomes short, and the probability for the carriers to be trapped becomes small. Therefore, a greater current can be generated, and a higher carrier mobility may be obtainable. So, according to the active device 20 of the present embodiment, it is possible to realize fast switching and large current driving.

On the other hand, if the low resistance layer 6 is formed to cover the whole channel region, as in the active device 20, the current may increase in the OFF state. In this case, the low resistance layer 6 may be made into an inter-digital shape as shown, for example, in FIG. 2B, or, although not illustrated, into a grating shape or a disk shape to adjust the width of the low resistance layer 6 in the channel length direction and suppress the magnitude of the current in the OFF state.

Switching performance of an active device is

expressed by the following formula in terms of  
switching frequency  $f_c$ , as suggested in Appl. Phys.  
Lett., vol. 76, No. 14, 3 April (2000), 1941-1943.

$$f_c = \mu V_d / 2\pi L^2$$

5                where  $\mu$  represents the carrier mobility;  $V_d$   
represents the source-drain voltage, and  $L$  represents  
the channel length. It is reported that this formula  
reproduces experimental results very well.

              In the active device 20 of the present  
10   embodiment, when a voltage is applied between the  
source electrode 3 and the drain electrode 4, carriers  
enter the low resistance layer 6 from the first  
electrode 3 via the organic semiconductor layer 5, are  
injected into the organic semiconductor layer 5 from  
15   the low resistance layer 6, and flow to the second  
electrode 4. Accordingly, it is easily possible to make  
the channel short. In addition, concerning the  
fabricating process of the active device 20 of the  
present embodiment, there is only one more step of  
20   forming the film of the low resistance layer 6 besides  
those steps for forming the thin film FET active device  
of the related art (refer to FIG. 27), so the  
fabrication is easy.

              Since the active device 20 of the present  
25   embodiment is the same as the thin film FET active

device of the related art (refer to FIG. 27) except for an additional low resistance layer 6, the effect of the low resistance layer 6 in the present embodiment may be realized by just setting the resistance between the  
5 source electrode 3 and the drain electrode 4 in the active device 20 sufficiently small compared with that of the resistance between the source electrode 203 and the drain electrode 204.

For example, the resistance between the  
10 source electrode 3 and the drain electrode 4 in the active device 20 may be set less than one-tenth of the resistance between the source electrode 203 and the drain electrode 204, if the active device 20 has the same distance between the first electrode 3 and the  
15 second electrode 4, the same channel length, and the same constituent parts but the low resistance layer 6 as the thin film FET active device of the related art shown in FIG. 27.

In the active device 20 of the present  
20 embodiment, when a gate voltage is applied to the gate electrode 1, the channel region should reach the first electrode 3, the second electrode 4, and the low resistance layer 6. It is difficult to do this with a common inorganic semiconductor. In a common inorganic  
25 semiconductor, minority carriers in the semiconductor

layer are concentrated near the surface of the insulating layer, thereby forming a channel layer. For this reason, when using a common inorganic semiconductor, the source electrode 3 and the drain electrode 4 have to be formed to be smaller than the channel thickness.

With an organic semiconductor, although the mechanism of channel formation is still not yet clarified, it is known that the channel width may reach 10,000 nm, being thicker than the typical thickness (5,000 nm) of the source/drain electrode of a TFT device. Even if the channel width is 10,000 nm, in the active device 20 shown in FIG. 1, wherein the thickness of the source/drain electrode is formed to be 4,000 nm, and the semiconductor layer is formed to be 10,000 nm, because a TFT device having a channel length of 6,000 nm is obtained, and the channel is formed all over the semiconductor layer, it becomes possible to modulate the source-drain current by applying a gate voltage.

In the active device 20 of the present embodiment, both the distance from the first electrode 3 to the low resistance layer 6 and the distance from the second electrode 4 to the low resistance layer 6 are shorter than the distance between the source electrode 3 and the drain electrode 4, so, it is

possible to obtain a desired current to generate the ON state.

In practical use of the active device 20, either the first electrode 3 or the second electrode 4 needs to be formed thinner than the channel thickness. In doing this, it is possible to obtain a desired current to generate the ON state by controlling the current between the source electrode 3 and the drain electrode 4.

10           Generally, it is preferable that the first electrode 3 and the second electrode 4 be formed as thin as possible. This is also true for a TFT having a common structure. In a common TFT, the first electrode 3 and the second electrode 4 correspond to the source and drain electrodes, respectively, and the purpose of making the source and drain electrodes thin is to increase the degree of integration of the common TFT.

In the TFT having the structure described in the present embodiment, thin source and drain electrodes result in not only a higher degree of integration but also lower current in the OFF state, and therefore it is more important to make the first electrode 3 and the second electrode 4 thin in the TFT of the present embodiment, more so than in the common TFT. For example, the thickness of the first electrode

20

25

3 and the second electrode 4 may be adjusted, respectively, so that the ratio of the currents in the ON state and OFF state becomes the maximum.

In the present embodiment, the channel  
5 thickness is defined as below.

FIG. 3 is a partial sectional view of the active device 20 connected to power supplies. Turning on the power supplies to drive the active device 20, it is possible to measure the channel thickness of the  
10 active device 20.

In FIG. 3, a voltage supplied by the power supply 10 is applied to the gate electrode 1. The numeral 9 indicates a power supply generating a current between the source electrode 3 and the drain electrode  
15 4.

In measurement of the channel thickness, the materials and thickness of the gate insulating layer 2, the source electrode 3, drain electrode 4, as well as the material of the organic semiconductor layer 5 are  
20 set to have values as in practical use. Then, the thickness of the organic semiconductor layer 5 is changed from 10 nm to a few hundred nm, and the thickness of the organic semiconductor layer 5 making the source-drain current maximum is defined as the  
25 channel thickness.

In the active device 20 of the present embodiment, a substrate (for example, the substrate 8 in FIG. 12) is provided below the gate electrode 1 as viewed in FIG. 12. Preferably, this substrate is

5 flexible and formed from, for example, a resin selected from the group including styrene-based polymers such as copoly(styrene/butadiene), copoly(styrene/acrylonitrile), terpoly(styrene/acrylonitrile/butadiene),

10 copoly(styrene/maleic acid), and copoly(styrene/acrylic acid), polyethylene-based resins such as copoly(ethylene/vinyl acetate) and chlorinated polyethylenes, polypropylene, vinyl chloride-based resins such as copoly(vinyl chloride/vinyl acetate),

15 polyester alkyd resins, polyamides, polyurethanes, polycarbonates, polyallylates, polysulfones, diallyl phthalate resin, poly(vinylbutyral) resin, polyether resins, polyester resins, acrylic resin, silicone resin, epoxy resins, phenolic resin, urea resin, melamine

20 resin, fluorocarbon resins such as PFA, PTFE, and PVDF, Parylene resin, polyimide resins, and photo-setting resins such as epoxyacrylates and urethane acrylates.

The active device 20 of the present embodiment may be fabricated, for example, as described

25 below. First, the gate electrode 1 is formed on an



insulating substrate (not shown), then the gate  
insulating film 2 is formed on the gate electrode 1,  
and then, the first electrode (source electrode) 3 and  
the second electrode (drain electrode) 4 are formed on  
5 the gate insulating layer 2. The source electrode 3 and  
the drain electrode 4 are arranged in the same plane  
and at a certain interval. Then the organic  
semiconductor layer 5 is formed to be disposed in the  
interval between the source electrode 3 and the drain  
10 electrode 4 and cover the upper surfaces of the source  
electrode 3 and the drain electrode 4. Further, on the  
organic semiconductor layer 5, the low resistance layer  
6 is formed from a material having an electrical  
resistance lower than that of the organic semiconductor  
15 layer 5.

#### The Second Embodiment

FIG. 4 shows a sectional view of an active  
device 20a according to a second embodiment of the  
20 present invention.

As shown in FIG. 4, the active device 20a  
includes a gate electrode 1, an insulating layer 2  
(gate insulating film) on the gate electrode 1, a first  
electrode 3 (source electrode) and a second electrode 4  
25 (drain electrode) on the insulating layer 2 arranged at

an interval in the same plane, an organic semiconductor layer 5a disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the upper surfaces of the source electrode 3 and the drain electrode 4, and a low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5 and formed above the organic semiconductor layer 5.

Preferably, the organic semiconductor layer 5a is formed from the same organic semiconductor materials as described in the first embodiment, but the organic semiconductor layer 5a includes dielectric materials.

Preferably, the dielectric materials may be from styrene-based polymers such as copoly(styrene/butadiene), copoly(styrene/acrylonitrile), terpoly(styrene/acrylonitrile/butadiene), copoly(styrene/maleic acid), and copoly(styrene/acrylic acid), polyethylene-based resins such as copoly(ethylene/vinyl acetate), and chlorinated polyethylenes, polypropylene, vinyl chloride-based resins such as copoly(vinyl chloride/vinyl acetate), polyester alkyd resins, polyamides, polyurethanes, polycarbonates, polyallylates, polysulfones, diallyl

phthalate resin, poly(vinylbutyral) resin, polyether resins, polyester resins, acrylic resin, silicone resin, epoxy resins, phenolic resin, urea resin, melamine resin, fluorocarbon resins such as PFA, PTFE, and PVDF, 5 Parylene resin, polyimide resins, and photo-setting resins such as epoxyacrylates and urethane acrylates, a metal oxide film produced by baking a solution obtained via hydrolysis of a metal alkoxide represented by one of the general formulas  $M(OR)_n$  and  $MR(OR')_{n-1}$ , in which 10 each of R and R' is an organic group such as an alkyl group and a phenyl group, M is a metal in one of IVA through VIIA groups, VIII group, and IB through VIB groups of the periodic table, and n is an ionic valence of the metal M, an oxide of one of Al, Ta, and W, Si, 15 and a nitride of Si.

FIG. 5 shows a chemical formula representing an organic semiconductor material used in the second embodiment of the present invention.

For example, the organic semiconductor layer 20 5a includes the organic semiconductor material represented by the chemical formula shown in FIG. 5 and a polycarbonate dielectric material. In the organic semiconductor layer 5a, for example, the organic semiconductor material amounts to 90% by weight, and 25 the polycarbonate amounts to 10% by weight, and the

polycarbonate is dispersed in the organic semiconductor material.

The low resistance layer 6, source electrode 3, drain electrode 4, the gate electrode 1, and the  
5 insulating layer 2 are formed from the materials as described in the first embodiment.

In the present invention, the "dielectric material" means a material having a dielectric constant greater than 1.5 determined according to the ASTM-D150  
10 (American Society for Testing and Materials) standard (the frequency is 1 kHz). Therefore, even if the organic semiconductor material of the organic semiconductor layer 5a does not explicitly include dielectric materials, as long as the dielectric  
15 constant of the organic semiconductor material is greater than 1.5, such a organic semiconductor layer is within the scope of the present invention.

The dielectric materials can be dispersed in the organic semiconductor material, for example, by  
20 molecule dispersion, or be dispersed after making the dielectric materials into fine particles.

In the active device 20a, the low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5a is formed to  
25 cover the whole channel region, so it is possible to

make the channel short, and therefore, a greater current and higher carrier mobility are obtainable. So, according to the active device 20a, it is possible to realize fast switching and large current driving.

5                Since the organic semiconductor layer 5a is formed from organic materials, vaporization or coating can be used to form the organic semiconductor layer 5, and this can effectively reduce the costs of the manufacturing equipment and the device.

10              Further, since the organic semiconductor layer 5a includes dielectric materials, although the mechanism concerned has not been clarified, when a gate voltage is applied to the active device 20a, the channel length thereof (the thickness of the channel  
15 layer) can be made greater than the typical thickness of the source electrode 3 and drain electrode 4 of the active device 20a (a TFT device), and as a result, when the low resistance layer 6 is formed above the source electrode 3, the drain electrode 4, and the organic  
20 semiconductor layer 5a, the channel is in contact with the low resistance layer 6, enabling driving by a large current.

                In addition, by including dielectric materials in the organic semiconductor layer 5a, the  
25 resistance of the organic semiconductor layer 5a

increases, and resultantly, it becomes easy to control the magnitude of the current in the OFF state. For example, the amount of the dielectric materials may be appropriately determined according to a target value of  
5 the current in the OFF state.

### The Third Embodiment

FIG. 6 shows a sectional view of a configuration of an active device 30 according to the  
10 third embodiment of the present invention.

As shown in FIG. 6, the active device 30 includes a gate electrode 1, a gate insulating film 2 on the gate electrode 1, a source electrode 3 and a drain electrode 4 on the gate insulating film 2  
15 arranged at an interval in the same plane, an organic semiconductor layer 5 disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the upper surface of the drain electrode 4, and a low resistance layer 6 having an electrical  
20 resistance lower than that of the organic semiconductor layer 5 and formed on the source electrode 3 and the organic semiconductor layer 5.

As shown in FIG. 6, in the active device 30 of the present embodiment, the source electrode 3 is in  
25 contact with the low resistance layer 6. Due to this,

it is possible to make the channel length of the active device 30 short.

It will be appreciated that it is also possible to make the drain electrode 4 in contact with the low resistance layer 6. In this case, the organic semiconductor layer 5 needs to be formed to cover the source electrode 3 instead of the drain electrode 4. This configuration has the same effects as that of the first embodiment.

10           The active device 30 of the present embodiment may be fabricated, for example, as described below. First, the gate electrode 1 is formed on an insulating substrate (not shown), then the gate insulating film 2 is formed on the gate electrode 1, and then, the source electrode 3 and the drain electrode 4 are formed on the gate insulating film 2. The source electrode 3 and the drain electrode 4 are arranged in the same plane and at a certain interval. Then the organic semiconductor layer 5 is formed while the source electrode 3 is masked. The organic semiconductor layer 5 is disposed in the interval between the source electrode 3 and the drain electrode 4, and covers the upper surface of the drain electrode 4. Then the mask is removed and on the organic semiconductor layer 5 and the source electrode 3, the

15

20

25

low resistance layer 6 is formed from a material having an electrical resistance lower than that of the organic semiconductor layer 5.

The active device 30 can also be fabricated, for example, by forming the source electrode 3 higher than the thickness of the organic semiconductor layer 5, and then forming the organic semiconductor layer 5 on the drain electrode 4.

10                    The Fourth Embodiment

FIG. 7 shows a sectional view of an active device 40 according to the fourth embodiment of the present invention.

As shown in FIG. 7, the active device 40 includes a gate electrode 1, a gate insulating film 2. on the gate electrode 1, a source electrode 3 and a drain electrode 4 on the gate insulating film 2, an organic semiconductor layer 5 disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the source electrode 3 and the drain electrode 4, and a low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5 and formed on the organic semiconductor layer 5. The active device 40 is different from the active device 20 in the first



embodiment in the respect that there is a high resistance layer 7 formed between the source electrode 3 and the organic semiconductor layer 5. The resistance of the organic semiconductor layer 5 is determined so that carriers in the organic semiconductor layer 5 are able to tunnel through the high resistance layer 7 when a sufficiently high gate voltage is applied to the gate electrode 1.

FIG. 8 is a sectional view for explaining the fabrication steps of the active device 40 in FIG. 7.

When fabricating the active device 40 of the present embodiment, it is desirable to measure the electrical resistance between the source electrode 3 and the drain electrode 4 before the low resistance layer 6 is formed; then the high resistance layer 7 and the low resistance layer 6 are formed so that the electrical resistance between the source electrode 3 and the low resistance layer 6 is equal to or lower than that between the source electrode 3 and the drain electrode 4.

FIG. 9 is a partial sectional view of the active device 40 connected to power supplies.

In the device shown in FIG. 9, a voltage output from a power supply 10 is applied to the gate electrode 1, and thereby the resistance of the organic

semiconductor layer 5 decreases. Accordingly, if there is a sufficiently high potential drop across the gate insulating film 2, a tunneling current is generated in the gate insulating film 2, and a desired current is  
5 obtained to generate the ON state. When the power supply 10 is not in operation, the gate insulating layer 2 blocks the movement of carriers, making it possible to reduce the current in the OFF state. In this way, with the active device 40 of the present  
10 embodiment, it is possible to obtain a high current ratio in ON/OFF states. In FIG. 9, the numeral 9 indicates a power supply generating a current between the source electrode 3 and the drain electrode 4.

Preferably, the high resistance layer 7 is  
15 formed from, for example, at least one resin selected from the group including thermoplastic resins such as styrene-based polymers such as  
copoly(styrene/butadiene),  
copoly(styrene/acrylonitrile),  
20 terpoly(styrene/acrylonitrile/butadiene),  
copoly(styrene/maleic acid), and copoly(styrene/acrylic acid), polyethylene-based resins such as  
copoly(ethylene/vinyl acetate), and chlorinated  
polyethylenes, polypropylene, vinyl chloride-based  
25 resins such as copoly(vinyl chloride/vinyl acetate),

polyester alkyd resins, polyamides, polyurethanes,  
polycarbonates, polyallylates, polysulfones, diallyl  
phthalate resin, poly(vinylbutyral) resin, polyether  
resins, polyester resins, acrylic resin, silicone resin,  
5 epoxy resins, phenolic resin, urea resin, melamine  
resin, fluorocarbon resins such as PFA, PTFE, and PVDF,  
Parylene resin, polyimide resins, and photo-setting  
resins such as epoxyacrylates and urethane acrylates,  
or a metal oxide produced via oxidation of a surface of  
10 an electrode layer formed from the metal.

Since the high resistance layer 7 is formed  
from polymers, coating or other techniques can be used  
to form the layer 7. In addition, the high resistance  
layer 7 can be formed, for example, by surface  
15 oxidation of the electrode layer, which results in  
reduced costs of the manufacturing equipment and the  
device.

Preferably, the high resistance layer 7 is  
formed from, for example, a metal oxide film produced  
20 by coating and baking a solution obtained via  
hydrolysis of a known metal alkoxide represented by one  
of the general formulas  $M(OR)_n$  and  $MR(OR')_{n-1}$ , wherein  
each of R and R' is an organic group such as an alkyl  
group and a phenyl group, M is a metal in one of IVA  
25 through VIIA groups, VIII group, and IB through VIB

groups of the periodic table, and  $n$  is an ionic valence of the metal  $M$ .

Since the high resistance layer 7 is formed from metal oxide films obtained by coating or heat-drying the solution produced in hydrolysis of metal alkoxide, the high resistance layer 7 can be formed without the complicated vacuum processing, and therefore, costs of the manufacturing equipment and the device can be reduced.

Particularly, since a polyimide resin has both good electric resistance and good solvent resistance, a polyimide resin may be preferably used as the insulating layer 2 and the high resistance layer 7, and even if a material dissolved or dispersed in an organic solvent is applied on the resin, the resin is not be seriously damaged.

It is explained in the above description that the high resistance layer 7 is disposed between the source electrode 3 and the organic semiconductor layer 5 as illustrated. But the present invention is not limited to this. The high resistance layer 7 may also be disposed between the source electrode 3 and the organic semiconductor layer 5, and/or between the drain electrode 4 and the organic semiconductor layer 5, and/or between the low resistance layer 6 and the

organic semiconductor layer 5. The above configurations have the same effects as that described above.

#### The Fifth Embodiment

5           FIG. 10 shows a sectional view of an active device 50 according to a fifth embodiment of the present invention.

As shown in FIG. 10, the active device 50 includes a gate electrode 1, a gate insulating film 2  
10 on the gate electrode 1, a source electrode 3 and a drain electrode 4 on the gate insulating film 2, an organic semiconductor layer 5 disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the drain electrode 4, a high resistance  
15 layer 7 disposed between the drain electrode 4 and the organic semiconductor layer 5, and a low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5 and formed on the organic semiconductor layer 5 and the source electrode  
20 3.

The active device 50 of the present embodiment is different from the active device 40 of the fourth embodiment in the respect that the source electrode 3 is in contact with the low resistance layer  
25 6 in the active device 50, and the interface between

the source electrode 3 and the low resistance layer 6 is of rectification capability.

With the above configuration, it is possible to make the channel length short, and to obtain a high  
5 ON/OFF ratio.

The rectification capability is explained below while considering the case of contact between a metal and a p-type semiconductor (hole transporting semiconductor).

10 FIGS. 11A through 11C are graphs showing rectification performance of the active device 50 according to the fifth embodiment of the present invention.

In FIGS. 11A through 11C, the symbol "M" indicates one of the source electrode 3, the drain  
15 electrode 4, and the low resistance layer 6; the symbol "S" indicates the organic semiconductor layer 5.

When the work function of M is higher than that of S, due to the contact of M and S, the band  
20 bends downward as shown in FIG. 11A...

Under this condition, if a negative voltage is applied to M, and a positive voltage is applied to S, as shown in FIG. 11B, the potential of M becomes lower relative to that of S, and therefore, the potential  
25 barrier becomes lower, and holes move toward M easily.

To the contrary, as shown in FIG. 11C, if a positive voltage is applied to M, and a negative voltage is applied to S, the potential of M becomes higher relative to that of S, and therefore, the  
5 potential barrier becomes higher, and it becomes difficult for holes to move to M.

In the present invention, the electrodes are formed from the materials described in the first embodiment. Material selection of the electrodes may be  
10 made from the view of the work function of a material. For example, if the semiconductor material (here, the organic semiconductor layer 5) is a hole transporting material, the electrodes may be made from metals having low work functions, such as Mg, Al, Cr, Ag, and so on;  
15 and if the semiconductor material is an electron transporting material, the electrodes may be made from metals having high work functions, such as Au, Pt and so on.

When configuring a device similar to that in  
20 FIG. 9 but including the active device 20, if the organic semiconductor layer 5 is formed from a hole transporting material, and the source electrode 3 and the drain electrode 4 are formed from a material having a work function lower than that of the organic  
25 semiconductor layer 5, rectification interfaces can be

formed between one of the electrodes and the organic semiconductor layer 5. Since the potential barrier becomes higher at the interface between the source electrode 3 and the organic semiconductor layer 5, it is difficult for carriers to move, and therefore the current in the OFF state can be suppressed.

#### The Sixth Embodiment

FIG. 12 shows a sectional view of an active device 60 according to the sixth embodiment of the present invention.

As shown in FIG. 12, the active device 60 includes a substrate 8, a source electrode 3 and a drain electrode 4 at an interval in the same plane on the substrate 8, an organic semiconductor layer 5 disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the upper surfaces of the source electrode 3 and the drain electrode 4, a low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5 and formed above the organic semiconductor layer 5, a gate insulating film 2 on the low resistance layer 6, and a gate electrode 1 on the gate insulating film 2.

FIG. 13 shows a configuration of an active



device 61 according to the sixth embodiment of the present invention.

As shown in FIG. 13, in the active device 61, a high resistance layer 7 as described in previous  
5   embodiments may be disposed, for example, between the drain electrode 4 and the organic semiconductor layer 5, as illustrated, to allow carriers in the organic semiconductor layer 5 to tunnel through the high resistance layer 7 when a sufficiently high gate  
10   voltage is applied to the gate electrode 1.

As mentioned above, the high resistance layer 7 may be formed between the source electrode 3 and the organic semiconductor layer 5, and/or between the drain electrode 4 and the organic semiconductor  
15   layer 5, and/or between the low resistance layer 6 and the organic semiconductor layer 5.

In the active devices 60 and 61 of the present embodiment, since the low resistance layer 6 having an electrical resistance lower than that of the  
20   organic semiconductor layer 5 is disposed in the same manner as the active device 20 of the first embodiment, it becomes easy to make the channel short. In the active devices 60 and 61, if the channel is made short, the distance that carriers move becomes short, and the  
25   probability for the carriers to be trapped becomes

small. Therefore a greater current can be generated,  
and higher carrier mobility is obtainable. So,  
according to the active devices 60 and 61 of the  
present embodiment, it is possible to realize fast  
5 switching and large current driving.

Further, because the high resistance layer 7  
is disposed between the drain electrode 4 and the  
organic semiconductor layer 5, as shown in FIG. 13, or  
between the source electrode 3 and the organic  
10 semiconductor layer 5, or between the low resistance  
layer 6 and the organic semiconductor layer 5, carriers  
in the organic semiconductor layer 5 are allowed to  
tunnel through the high resistance layer 7 when a  
sufficiently high gate voltage is applied to the gate  
15 electrode 1.

In a manner the same as the active device 40  
of the fourth embodiment, in the active devices 60 and  
61, when a gate voltage is applied to the gate  
electrode 1, the resistance of the organic  
20 semiconductor layer 5 decreases. Accordingly, there is  
a sufficiently large potential drop across the gate  
insulating film 2, a tunneling current is generated in  
the gate insulating film 2, and a desired current is  
obtained to generate the ON state. When the gate  
25 voltage is not applied, the gate insulating layer 2

blocks the movement of carriers, making it possible to reduce the current in the OFF state. In this way, with the active device 61 of the present embodiment, it is possible to obtain a high current ratio in ON/OFF states.

#### The Seventh Embodiment

FIG. 14 shows a sectional view of an active device 70 according to the seventh embodiment of the present invention.

In FIG. 14, the active device 70 includes a substrate 8, a low resistance layer 6 on the substrate 8, an organic semiconductor layer 5 on the low resistance layer 6, a source electrode 3 and a drain electrode at an interval in the same plane on the organic semiconductor layer 5, a gate insulating film 2 disposed in the interval between the source electrode 3 and the drain electrode 4 and covering the upper surfaces of the source electrode 3 and the drain electrode 4, and a gate electrode 1 on the gate insulating film 2. The electrical resistance of the low resistance layer 6 is lower than that of the organic semiconductor layer 5.

FIG. 15 shows a configuration of an active device 71 according to the seventh embodiment of the

present invention.

As shown in FIG. 15, in the active device 71, a high resistance layer 7 as described in previous embodiments may be formed, for example, between the  
5 source electrode 3 and the organic semiconductor layer 5 to allow carriers in the organic semiconductor layer 5 to tunnel through the high resistance layer 7 when a sufficiently high gate voltage is applied to the gate electrode 1. As mentioned above, the high resistance  
10 layer 7 may also be formed between the drain electrode 4 and the organic semiconductor layer 5, and/or between the low resistance layer 6 and the organic semiconductor layer 5.

In the active device 71 of the present  
15 embodiment, since the low resistance layer 6 having an electrical resistance lower than that of the organic semiconductor layer 5 is formed in a manner the same as the active device 20 of the first embodiment, it becomes easy to make the channel short. In the active  
20 device 71, if the channel is made short, the distance that carriers move becomes short, and the probability for the carriers to be trapped becomes small. Therefore a greater current can be generated, and higher carrier mobility is obtainable. So, according to the active  
25 device 71 of the present embodiment, it is possible to

realize fast switching and large current driving.

Further, because the high resistance layer 7 is disposed between the source electrode 3 and the organic semiconductor layer 5, as shown in FIG. 15, or between the drain electrode 4 and the organic semiconductor layer 5, or between the low resistance layer 6 and the organic semiconductor layer 5, carriers in the organic semiconductor layer 5 are allowed to tunnel through the high resistance layer 7 when a sufficiently high gate voltage is applied to the gate electrode 1.

In a manner the same as the active device 40 of the fourth embodiment, in the active devices 70 and 71, when a gate voltage is applied to the gate electrode 1, the resistance of the organic semiconductor layer 5 decreases. Accordingly, there is a sufficiently large potential drop across the gate insulating film 2, a tunneling current is generated in the gate insulating film 2, and a desired current is obtained to generate the ON state. When the gate voltage is not applied, the gate insulating layer 2 blocks the movement of carriers, making it possible to reduce the current in the OFF state. In this way, with the active devices 70 and 71 of the present embodiment, it is possible to obtain a high current ratio in ON/OFF

states.

#### The Eighth Embodiment

FIG. 16 shows a sectional view of an active  
5 device 80 according to the eighth embodiment of the  
present invention.

In FIG. 16, the active device 80 includes a  
substrate 8, a gate electrode 1 on the substrate 8, a  
gate insulating film 2 on the gate electrode 1, a low  
10 resistance layer 6 on the gate insulating film 2, an  
organic semiconductor layer 5 on the low resistance  
layer 6, and a source electrode 3 and a drain electrode  
4 at an interval in the same plane on the organic  
semiconductor layer 5. The electrical resistance of the  
15 low resistance layer 6 is lower than that of the  
organic semiconductor layer 5.

FIG. 17 shows a configuration of an active  
device 81 according to the eighth embodiment of the  
present invention.

20 As shown in FIG. 17, the active device 81  
may also have a configuration in which the two opposite  
ends of the low resistance layer 6 are covered by the  
organic semiconductor layer 5.

FIG. 18 shows a configuration of an active  
25 device 82 of the eighth embodiment of the present

invention.

As shown in FIG. 18, in the active device 82, a high resistance layer 7 as described in previous embodiments may be formed, for example, between the source electrode 3 and the organic semiconductor layer 5 to allow carriers in the organic semiconductor layer 5 to tunnel through the high resistance layer 7 when a sufficiently high gate voltage is applied to the gate electrode 1. As mentioned above, the high resistance layer 7 may also be formed between the drain electrode 4 and the organic semiconductor layer 5, and/or between the low resistance layer 6 and the organic semiconductor layer 5.

According to the active devices 80, 81, and 82 of the eighth embodiment, the gate electrode 1, the gate insulating film 2, the low resistance layer 6, the organic semiconductor layer 5, and the source electrode 3 and the drain electrode 4 are formed sequentially, so by controlling the current between the source electrode 3 and the drain electrode 4, it is possible to obtain a desired current to generating the ON state. In addition, since the channel region is formed on the surface of the low resistance layer 6, the active devices 80 through 82 are not subjected to constraint in channel thickness as mentioned above. So the active devices 80

through 82 may also be realized with an inorganic semiconductor material.

Further, when the organic semiconductor layer 5 has ohmic contact with the source electrode 3, or the drain electrode 4, or the low resistance layer 6, the potential barrier at any of these surfaces is lowered, making holes move easily and thus generating large current.

In order to obtain ohmic contact, when using a hole transporting organic semiconductor to form the organic semiconductor layer 5, it is desirable to make the work function of the organic semiconductor layer 5 lower than the source electrode 3, the drain electrode 4, and the low resistance layer 6; on the other hand, when using an electron transporting organic semiconductor for the organic semiconductor layer 5, it is desirable to make the work function of the organic semiconductor layer 5 higher than the source electrode 3, the drain electrode 4, and the low resistance layer 6. This conclusion is also true to active devices in other embodiments of the present invention.

#### The Ninth Embodiment

FIG. 19 is a partial sectional view of an EL (electroluminescent) display device 90 according to the



ninth embodiment of the present invention.

As shown in FIG. 19, the EL display device 90 of the present embodiment includes a common flexible transparent substrate 27, and a pair of active devices and a light emission element arranged in a matrix manner on the substrate 27.

In the EL display device 90 of the present embodiment, each active device includes a gate electrode 21 on the substrate 27, a gate insulating film 22 covering ends and the upper surface of the gate electrode 21, a source electrode 23 and a drain electrode 24 on the gate insulating film 22 arranged at a certain interval in the same plane, an organic semiconductor layer 25 disposed in the interval between the source electrode 23 and the drain electrode 24, and a low resistance layer 26 having an electrical resistance lower than that of the organic semiconductor layer 25 and formed above the organic semiconductor layer 25.

Each light emission element includes a transparent electrode 28 on the substrate 27, an electroluminescent layer 29 on the transparent electrode 28, and a cathode 31 on the electroluminescent layer 29.

In addition, the source electrode 23 is

electrically connected with the transparent electrode  
28 through a power supply 32.

With the above configuration, it is possible  
to provide a display device at low cost but with good  
5 visibility and low power consumption.

The transparent electrode 28, for example,  
is formed from ITO (Indium Tin Oxide). Generally, the  
cathode 31 is formed from a material of a small work  
function, for example, Li, LiF, Ba, Mg, and so on, so  
10 as not to hinder movement of carriers. It is preferable  
that the value of the work function be less than 3.0 eV.  
Because these materials are unstable in air, it is  
preferable to form a stabilizing film on the surfaces  
of these materials. The stabilizing film is made from  
15 materials stable in the air, for example, Ag, or Al.

The electroluminescent layer 29, for example,  
is formed from an organic semiconductor material  
selected from the group including Alq<sub>3</sub> and derivatives  
thereof, fluorenone-based compounds and derivatives  
20 thereof, quinone-based compounds and derivatives  
thereof, indenone-based compounds and derivatives  
thereof, hydrazone-based compounds and derivatives  
thereof, stilbene and derivatives thereof, pyrazoline  
and derivatives thereof, phenylamine compounds and  
25 derivatives thereof, pyrene-based compounds and

derivatives thereof, and vinyl group-containing compounds and derivatives thereof, such as N-vinylcarbazole and polyvinylanthracene.

Alternatively, the electroluminescent layer  
5 29 is formed from an inorganic semiconductor material that contains an element in one of IVA through VIIA groups, VIII group, and IB through VIB groups of the periodic table, for example, a compound containing strontium, gallium, and sulfur in which cerium is doped,  
10 represented by  $\text{SrGa}_2\text{S}_4:\text{Ce}$ .

#### The 10th Embodiment

This embodiment relates to a liquid crystal display device including active devices as described in  
15 the previous embodiments. With such a liquid crystal display device, it is possible to provide a display device at low cost but with good visibility and low power consumption.

FIG. 20 shows an example of a circuit  
20 diagram of the liquid crystal display device according to the 10th embodiment of the present invention.

As shown in FIG. 20, according to the gray-level data of every pixel, gate voltages from the gray-level signal line are applied to gate electrodes of  
25 active device. From the scanning line, a voltage signal

having ON levels and OFF levels alternatively and subsequently is supplied and is applied to subsequent lines. After scanning of one screen is finished, scanning of the next screen is started. To support motion picture display, preferably, the scanning frequency is greater than 50 Hz. The condenser shown in FIG. 20 serves the function of charging the liquid crystal cell during the transition from one screen to another screen so as to maintain the gray-level voltage in this period.

#### The 11th embodiment

This embodiment relates to a calculating device including active devices as described in the previous embodiments into a NOT circuit, or a NAND circuit, or a NOR circuit.

FIGs. 21A through 21C are logic circuits of the calculating device according to the 11th embodiment of the present invention, where FIG. 21A shows a NOT circuit (inverter circuit), FIG. 21B shows a NAND circuit, and FIG. 21C shows a NOR circuit.

As shown in FIGs. 21A through 21C, a first MOS transistor and a second MOS transistor are included in the NOT circuit, the NAND circuit, and the NOR circuit, respectively. The first MOS transistor

functions as an active device having an organic semiconductor layer formed from a hole transporting semiconductor material. The second MOS transistor functions as another active device having an organic semiconductor layer formed from an electron transporting semiconductor material.

For example, in the NOT circuit, when the input voltage is +5 V, the second MOS transistor is ON, the first MOS transistor is OFF, and the output voltage is 0. Or, when the input voltage is 0V, the second MOS transistor is OFF; since the voltage of the power supply is +5 V, the potential difference between the source and drain of the first MOS transistor is 5 V, so the output voltage is +5 V.

The NAND circuit and the NOR circuit operate in the similar way as the NOT circuit.

Therefore, according to the present embodiment, the calculating device of the present embodiment includes active devices of the previous embodiments into a NOT circuit, a NAND circuit, and a NOR circuit, and further the NOT circuit inverts the input voltage, the NAND circuit inverts the logic AND, and the NOR circuit inverts the logic OR, so it is possible to provide a calculating device at low cost able to perform calculation using the input signals and

output the calculation results.

Example 1

FIG. 22 is a partial sectional view of a  
5 first example of the active device of the present  
invention. The active device in FIG. 22 is the same as  
that shown in FIG. 1 (active device 20).

The active device shown in FIG. 22 was  
fabricated according to the following steps.

10 Step 1: the gate electrode 1 was formed from  
aluminum to a thickness of 50 nm on a not-shown  
substrate.

Step 2: the gate insulating film 2 was  
formed from  $\text{SiO}_2$  to a thickness of 100 nm on the gate  
15 electrode 1.

Step 3: a not-shown adhesive layer was  
formed from Cr to a thickness of 10 nm on the gate  
insulating layer 2.

Step 4: the source electrode 3 and the drain  
20 electrode 4 were formed from Au both to a thickness of  
50 nm on the gate insulating layer 2 separated from  
each other by a distance of 40 nm.

Step 5: on the source electrode 3 and the  
drain electrode 4, and on the gate insulating layer 2  
25 between the source electrode 3 and the drain electrode

4, a hole transporting organic semiconductor layer 5 was formed from poly-3-octylthiophene to a thickness of 80 nm from the top of the source electrode 3 and the drain electrode 4.

5                   Step 6: on the organic semiconductor layer 5, the low resistance layer 6 was formed from Au to a thickness of 50 nm.

The device fabricated following the above steps had a channel length of 10 nm.

10

#### Example 2

An active device the same as the active device 30 shown in FIG. 6 was fabricated following the same steps and using the same parameters as shown in  
15   example 1.

#### Example 3

FIG. 23 is a partial sectional view of a third example of the active device of the present  
20   invention. The active device in FIG. 23 is the same as the active device 40 in FIG. 7.

The device shown in FIG. 23 was fabricated following the same steps using the same parameters as shown in example 1, except as follows. In fabrication  
25   of this device, the high resistance layer 7 was formed

to 50 nm by coating a solution prepared by solving poly (vinyl butyral) into ethanol.

#### Example 4

5           An active device of the same configuration as that shown in FIG. 23 was fabricated in a way different from that in example 3.

          In this example, the device shown in FIG. 23 was fabricated according to the following steps.

10           Step 1: the gate electrode 1 was formed from aluminum to 30 nm on a not-shown substrate.

          Step 2: the gate insulating film 2 was formed from  $\text{SiO}_2$  to 100 nm on the gate electrode 1.

          Step 3: a not-shown adhesive layer was  
15   formed from Cr to a thickness of 10 nm on the gate insulating layer 2 except in an area where the drain electrode 4 would be formed.

          Step 4: first the source electrode 3 was formed from Al to 30 nm on the gate insulating layer 2,  
20   then after surface oxidation of the source electrode 3, a layer of  $\text{Al}_2\text{O}_3$  is obtained acting as the high resistance layer 7.

          Step 5: the drain electrode 4 was formed from Au to 20 nm on the gate insulating layer 2 in the  
25   area covered by the adhesive layer and separated from



the source electrode 3 by a distance of 35 nm.

Step 6: on the source electrode 3 and the drain electrode 4, and on the gate insulating layer 2 between the source electrode 3 and the drain electrode 4, a hole transporting organic semiconductor layer 5 was formed from poly-3-octylthiophene to 80 nm from the top of the source electrode 3 and the drain electrode 4.

Step 7: on the organic semiconductor layer 5, the low resistance layer 6 was formed from Au to a thickness of 50 nm.

The device fabricated following the above steps had a channel length of 10 nm.

#### Example 5

15 An active device the same as the active device 20a shown in FIG. 4 was fabricated following the same steps as shown in example 1.

The device shown in FIG. 4 was fabricated according to the following steps.

20 Step 1: the gate electrode 1 was formed from aluminum to a thickness of 50 nm on a not-shown substrate.

Step 2: the gate insulating film 2 was formed from SiO<sub>2</sub> to a thickness of 100 nm on the gate electrode 1.

25

Step 3: a not-shown adhesive layer was formed from Cr to a thickness of 10 nm on the gate insulating layer 2.

Step 4: the source electrode 3 and the drain electrode 4 were formed from Au both to a thickness of 20 nm on the gate insulating layer 2 separated from each other by a distance of 40 nm.

Step 5: on the source electrode 3 and the drain electrode 4, and on the gate insulating layer 2 between the source electrode 3 and the drain electrode 4, an organic semiconductor layer 5a was formed to a thickness of 80 nm from the tops of the source electrode 3 and the drain electrode 4 from a material including an organic semiconductor material represented by the chemical formula shown in FIG. 5 and amounting to 90% by weight and a polycarbonate dielectric material dispersed in the organic semiconductor material and amounting to 10% by weight.

Step 6: on the organic semiconductor layer 5, the low resistance layer 6 was formed from Au to a thickness of 50 nm.

The device fabricated following the above steps had a channel length of 10 nm.

For comparison, a device including the active device shown in FIG. 27 was also fabricated. The fabrication procedure is the same as that shown in example 1 (FIG. 22), except the formation of the low  
5 resistance layer 6.

#### Performance Evaluation

The performance of the devices fabricated in the examples 1 through 5 as well as the example for  
10 comparison was measured.

##### (1). Examples 1 and 2

##### <Static performance measurement>

Setting the voltage of the first power  
15 supply 9 to be 0 V, 2 V, 4 V, and 8 V, respectively, and the voltage of the second power supply 10 to be 0 V, -4 V, and -8 V, respectively, the currents under various voltage conditions were measured.

##### 20 (2). Example 3

##### <Static performance measurement>

Setting the voltage of the first power  
supply 9 to be 8 V, and the voltage of the second power  
supply 10 to be 0 V, and -8 V, respectively, the  
25 current under these voltage conditions was measured.

Next, the voltage of the second power supply 10 was switched at a frequency of 1 Hz, and the current was measured after the device was driven continuously for 10 hours while being placed in a nitrogen flow.

5

(3). Example 4

<Static performance measurement>

Setting the voltage of the first power supply 9 to be 8 V, and the voltage of the second power supply 10 to be 0 V, and -8 V, respectively, the current under these voltage conditions was measured. Next, the voltage of the second power supply 10 was switched at a frequency of 1 Hz, and the current was measured after the device was driven continuously for 15 10 hours while being placed in a nitrogen flow.

(4). Example 5

<Static performance measurement>

Setting the voltage of the first power supply 9 to be 0 V, 2 V, 4 V, and 8 V, respectively, and the voltage of the second power supply 10 to be 0 V, -4 V, and -8 V, respectively, the currents under various voltage conditions were measured.

25

(5). Example for Comparison

<Static performance measurement>

Setting the voltage of the first power supply 9 to be 0 V, 4 V, 8 V, and 12 V, respectively, and the voltage of the second power supply 10 to be 0 V, -8 V, and -12 V, respectively, the currents under various voltage conditions were measured.

Results of the above measurements are summarized in tables in FIG. 24, FIG. 25, and FIG. 26.

While the present invention has been described with reference to specific embodiments chosen for purpose of illustration, it should be apparent that the invention is not limited to these embodiments, but numerous modifications could be made thereto by those skilled in the art without departing from the basic concept and scope of the invention.

Summarizing the effect of the invention, because the first resistance layer having an electrical resistance lower than that of the organic semiconductor layer is formed to cover the whole channel region, it is possible to make the channel short, and as a result, the distance that carriers have to move becomes short, and the probability for the carriers to be trapped becomes small. Therefore a greater current can be generated, and higher carrier mobility is obtainable. So, it is possible to realize fast switching and large

current driving. According to the active device of the present invention, thin first electrodes and second electrodes result in not only a higher degree of integration but also lower current in the OFF state, and the thickness of the first electrode and the second electrode may be adjusted so that the ratio of the currents in the ON state and the OFF state becomes the maximum.

Further, since the organic semiconductor layer may include dielectric materials, when a gate voltage is applied to the active device of the present invention, the channel length can be made greater than the typical thickness of the first electrode and the second electrode of the active device, and as a result, when the low resistance layer is formed above the first electrode, the second electrode, and the organic semiconductor layer, the channel is in contact with the low resistance layer, enabling large current driving.

In addition, by including dielectric materials in the organic semiconductor layer, the resistance of the organic semiconductor layer increases, and resultantly, it becomes easy to control the magnitude of the current in the OFF state.

In addition, because both the distance from the first electrode to the first resistance layer and

the distance from the second electrode to the first resistance layer are shorter than the distance between the source electrode and the drain electrode, it is possible to obtain a desired current to generate the ON  
5 state.

In addition, because either the first electrode or the second electrode is in contact with the first resistance layer, it is possible to make the channel length short.

10 In addition, because a second resistance layer is formed between the first electrode and the organic semiconductor layer, and/or between the second electrode and the organic semiconductor layer, and/or between the first resistance layer and the organic  
15 semiconductor layer, and carriers in the organic semiconductor layer are allowed to tunnel through the second resistance layer when a sufficiently high gate voltage is applied to the gate electrode, a large current is obtainable in the ON state, and the current  
20 in the OFF state can be reduced. Therefore, it is possible to obtain a high current ratio in ON/OFF states.

In addition, because one or more of the first electrode, the second electrode, and the first  
25 resistance layer is in contact with the organic

semiconductor layer, and the contact interface is of rectification capability, it is possible to make the channel length short, and to obtain a high ON/OFF ratio.

In addition, because the first resistance  
5 layer is formed to have one of a plate shape, an interdigital shape, a grating shape, and a disk shape, it is possible to reduce the current in the OFF state.

In addition, since the organic semiconductor layer is formed from organic materials, vaporization or  
10 coating can be used to form the organic semiconductor layer, effectively reducing the costs of the manufacturing equipment and the device.

In addition, since the first resistance layer is formed from conductive polymers, coating can  
15 be used to form this film, and this effectively reduces the costs of the manufacturing equipment and the device.

In addition, since the insulating layer is formed from polymers, coating or other techniques can be used to form this film. In addition, the insulating  
20 layer can be formed by surface oxidation of the electrode layer, and therefore, costs of the manufacturing equipment and the device can be reduced.

In addition, since the insulating layer is formed from metal oxide films obtained by coating or  
25 heat-drying the solution produced in hydrolysis of



metal alkoxide, the insulating layer can be formed without the complicated vacuum processing, and therefore, costs of the manufacturing equipment and the device can be reduced.

5           In addition, since the second resistance layer is formed from polymers, coating or other techniques can be used to form this film. In addition, the second resistance layer can be formed by surface oxidation of the electrode layer, and therefore, costs  
10 of the manufacturing equipment and the device can be reduced.

          In addition, since the second resistance layer is formed from metal oxide films obtained by coating or heat-drying the solution produced in  
15 hydrolysis of metal alkoxide, the second resistance layer can be formed without the complicated vacuum processing, and therefore, costs of the manufacturing equipment and the device can be reduced.

          According to the EL display device of the  
20 present invention, since active devices as described above are included, it is possible to provide an EL display device at low cost but with good visibility and low power consumption.

          According to the liquid crystal display  
25 device of the present invention, since active devices

as described above are included, it is possible to provide a liquid crystal display device at low cost but with good visibility and low power consumption.

According to the calculating device of the present invention, because semiconductor devices described above are included into a NOT circuit, a NAND circuit, and a NOR circuit, and further the NOT circuit inverts the input voltage, the NAND circuit inverts the logic AND, and the NOR circuit inverts the logic OR, it is possible to provide a calculating device at low cost and that is able to perform calculation using the input signals and output the calculation results.

This patent application is based on Japanese priority patent applications No. 2002-212685 filed on July 22, 2002, No. 2003-166765 filed on June 11, 2003, and No. 2003-190877 filed on July 3, 2003, the entire contents of which are hereby incorporated by reference.